

List of Publications

- [1] M. Kildemo and B. Dré villon, "Real time monitoring of the growth of transparent thin films by spectroscopic ellipsometry," Appl. Phys. Lett. **67**, 918-920 (1995).
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- [3] M. Kildemo, S. Deniau P. Bulkin and B. Dré villon, "Real time control of silicon alloy multilayers by multiwavelength ellipsometry," Thin Solid Films, **290-291**, 46-50 (1996).
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- [5] M. Kildemo, P. Bulkin, B. Dré villon and O. Hunderi, «Real time control by multi-wavelength ellipsometry of plasma deposited multilayers on glass using incoherent reflection model,» Appl. Opt. **36**, 6352-6359 (1997).
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- [11] M. Kildemo, R. Ossikovski and M. Stchakovsky, «Measurement of absorption edge of thick transparent substrates using incoherent reflection model and spectroscopic UV-Visible-near IR ellipsometry,» Thin Solid Films **313-314**, 108-113 (1998).
- [12] R. Etemadi, C. Godet, M. Kildemo, J. E. Bourée, R. Brenot, and B. Dré villon, «Dual-mode radio frequency/microwave plasma deposition of amorphous silicon oxide thin films,» J. Non. Crys. Solids **187**, 70 (1995).
- [13] M. Kildemo, R. Brenot and B. Dré villon, «Spectroellipsometric method for process monitoring semiconductor thin films and interfaces,» Appl. Opt. **37**, 5145-5149 (1998).
- [14] M. Kildemo, V. Dalsrud and O. Fostad, "Measurement of physical thicknesses in micro-machined structures consisting of glass and c-Si using FTIR-reflectance," Optical Engineering **38**, 1542-1552 (1999).
- [15] G. R Moriarty, M. Kildemo, J. T. Beechinor, M. Murtagh, P.V. Kelly, G. M. Crean, S. W. Bland, "Optical and structural properties of InGaP heterostructures," Thin Solid Films **364**, 244-248 (2000).
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- [29] M. Kildemo, "Optical properties of Silicon Carbide Polytypes below and around bandgap," *Thin Solid Films*, **455-456**, (2004) 187-195
- [30] M. Kildemo, "New spark-test device for material characterization," *Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment*, **530** (2004) 596.
- [31] M. Kildemo, S. Calatroni, M. Taborrelli, "Breakdown and field emission conditioning of Cu, Mo, and W," *Phys. Rev. ST Accel. Beams* **7** (2004) 092003.
- [32] M. Kildemo*, M. Juel and S. Raaen, "Properties of Tm-Pt(111) surface alloys," (submitted to *surf. Sci.* 2004)
- [33] M. Kildemo, Experimental study of the formation of the SmSiC surface alloy, To be submitted to *surf. Sci.* 2005.
- [34] M. Kildemo, Experimental study of the oxidation of the SmSiC alloy, to be submitted to *Surf. Sci.* 2005.

Patent

- [1] Procédé de mesure ellipsométrique, ellipsomètre et dispositif d'élaboration de couches les mettant en oeuvre, B. Drévilon, M.kildemo and R. Benferhat, FR-56398-Fn⁰9502263 (deposited the 27/02/95) under extension to Europe, Japan and USA.

Technical Reports (unpublished)

- [1] M. Kildemo, S. M. Nilsen and R. Ossikovski, "Investigation of measurement procedures to determine physical thickness of lightly doped epitaxial layer on doped c-Si substrates using FTIR-reflectance and ellipsometry," Internal SensoNor Technical Note.
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